

(54) HYBRID ORGANIC-INORGANIC (56) References Cited MICROMIRROR DEVICE AND METHOD OF MAKING A HYBRID MICRODEVICE U.S. PATENT DOCUMENTS

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- (73) Assignee: The Board of Trustees of the EP 2 784 566 Al $10/2014$ University of Illinois, Urbana, IL (US) OTHER PUBLICATIONS
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CPC $G02B$ 26/0841 (2013.01); $G02B$ 1/02 $(2013.01); B29C39/025 (2013.01);$ (Continued)
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Prior Publication Data (74) Attorney, Agent, or Firm — Brinks Gilson & Lione (57)

ABSTRACT ABSTRACT

ABSTRACT

A hybrid organic-inorganic micromirror device includes a micromirror comprising an inorganic material positioned above an elastomeric substrate. The micromirror is supported on an underside thereof by a conductive elastomeric support protruding from the elastomeric substrate. The conductive elastomeric support may function as a universal joint and is rendered electrically conductive by an electrically conductive coating thereon. A plurality of electrodes are disposed on the elastomeric substrate under the micromirror. The electrodes are spaced apart from each other and from the micromirror and are arranged around the conductive elas tomeric support. Each electrode comprises an inorganic material and is in electrical contact with an elastomeric
contact region protruding from the elastomeric substrate. When a voltage bias is applied between the micromirror and one or more of the electrodes, the micromirror is electrostatically actuated to move in a predetermined direction.

11 Claims, 6 Drawing Sheets

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- (52) **U.S. Cl.**
CPC .. *B29K 2083/00* (2013.01); *B29K 2105/0058* $(2013.01); B29L 2011/0058 (2013.01)$
- (58) Field of Classification Search CPC B29L 2011/0058; B29K 2083/00; B29K
	- 2105/0058; G02B 26/0841; G02B 1/02; G02B 26/08

USPC 359 / 221 . 2 See application file for complete search history.

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FIG. 1A

FIG. 1B

FIG . 4

FIG. 5

under 35 U.S.C. $$119(e)$ to U.S. Provisional Patent Appli-
cation No. 62/113.099. filed Feb. 6, 2015, which is hereby cally conductive coating. An uncured elastomer is applied to cation No. $62/113,099$, filed Feb. 6, 2015, which is hereby incorporated by reference in its entirety. $\frac{10}{10}$ the surface of the mold so as to fill the trenches and cover

The present disclosure is related generally to microfabrication technology and more specifically to a hybrid organiccation technology and more specifically to a hybrid organic-
inorganic substrate is fully cured to bond the functional inorganic
components to the conductive-coated protrusions.

and biomedical imaging. Common silicon-based MEMS FIGS. 2A-2C show exemplary steps in fabricating a micromirrors are designed with an optical reflector sus-
partially-cured elastomeric body that includes conductive micromirrors are designed with an optical reflector sus-
partially-cured elastomeric body that includes conductive
pended on a set of silicon torsional springs. Monolithic surface portions and may be used as a receiver sub pended on a set of silicon torsional springs. Monolithic surface portions and may be used as a receiver substrate; microfabrication including surface micromachining and FIGS 2D-2E show exemplary steps in fabricating inorga bulk micromachining processes are typically used to realize 35 such structures. However, the conventional design and fab-
rication approaches exhibit several fundamental challenges.
Silicon is susceptible to cleavage fracture under large defor-
components onto the receiver substrate f Silicon is susceptible to cleavage fracture under large defor-
momponents onto the receiver substrate followed by curing
mations as well as to fatigue failure under cyclic loading. In to form a hybrid organic-inorganic mic addition, microscale springs are usually needed to obtain a 40 FIGS. 3A-3D show the results of a finite element modal reasonable (low) stiffness due to the high elastic modulus of analysis of an exemplary micromirror devic reasonable (low) stiffness due to the high elastic modulus of analysis of an exemplary micromirror device. The microsilicon, and such small features are susceptible to photo-
mirror has four different resonant modes corres silicon, and such small features are susceptible to photo-
lithographic errors. Finally, complex mechanical design and
torsion, bending, shearing and tension/compression deforlithographic errors. Finally, complex mechanical design and torsion, bending, shearing and tension/compression defor-
fabrication steps are typically required to realize a two-axis mation of the conductive elastomeric supp fabrication steps are typically required to realize a two-axis mation of the conductive elastomeric support (universal micromirror. A gimbaled structure may provide an addi- 45 joint). tional degree of freedom to enable two-axis motion, but it FIG. 4 shows DC characteristics of the micromirror suffers from limitations, such as a large footprint and device for x-axis rotation, y-axis rotation and z-axis c suffers from limitations, such as a large footprint and device for x-axis rotation, y-axis rotation and z-axis com-
unequal frequency responses with respect to the two axes. pressive piston motion.

Described herein is a hybrid organic-inorganic micromir-

o Hz (A) and 1.2 Hz (B); the scale bars are

not device that has advantages over previous micromirror
 Δ DETAILED DESCRIPTION

DETAILED DESCRIPTION assemblies. Also described is a method of making a hybrid organic-inorganic microelectromechanical systems 55 organic-inorganic microelectromechanical
(MEMS) device.

ing an inorganic material positioned above an elastomeric mechanically and electrically integrated together are substrate. The micromirror is supported on an underside described herein. An exemplary micromirror device driven thereof by a conductive elastomeric support protruding from 60 by electrostatic actuation is based on a highl thereof by a conductive elastomeric support protruding from 60 the elastomeric substrate. The conductive elastomeric supthe elastomeric substrate. The conductive elastomeric sup-

port may function as a universal joint and is rendered and electrically connected to a conductive elastomeric uniport may function as a universal joint and is rendered and electrically connected to a conductive elastomeric uni-
electrically conductive by an electrically conductive coating versal joint (organic component). To realize thereon. A plurality of electrodes are disposed on the elas-
tomeric substrate under the micromirror. The electrodes are 65 printing-based microassembly techniques that allow the tomeric substrate under the micromirror. The electrodes are 65 spaced apart from each other and from the micromirror and are arranged around the conductive elastomeric support.

HYBRID ORGANIC-INORGANIC
MICROMIRROR DEVICE AND METHOD OF electrical contact with an elastomeric contact region pro-**CROMIRROR DEVICE AND METHOD OF** electrical contact with an elastomeric contact region pro-
MAKING A HYBRID MICRODEVICE truding from the elastomeric substrate. When a voltage bias truding from the elastomeric substrate. When a voltage bias is applied between the micromirror and one or more of the RELATED APPLICATIONS ⁵ electrodes, the micromirror is electrostatically actuated to move in a predetermined direction.

The present patent document claims the benefit of priority The method entails forming a plurality of trenches in a determine of a mold, and coating the trenches with an electri-
surface of a mold, and coating the trenches the surface. The uncured elastomer is partially cured to form FEDERALLY SPONSORED RESEARCH OR a tacky elastomeric body comprising protruding regions
DEVELOPMENT defined by the trenches. The protruding regions contact the defined by the trenches. The protruding regions contact the electrically conductive coating and attach thereto. The tacky This invention was made with government support under 15 elastomeric body is removed from the mold, and the elec-
contract number 917 NSF CMMI 13-51370 CAR awarded trically conductive coating is transferred with the pro by the National Science Foundation. The government has regions during the removal. The tacky elastomeric body may
be flipped over to form a receiver substrate comprising conductive-coated protrusions. A plurality of functional inorganic components are placed on the receiver substrate, TECHNICAL FIELD ²⁰ inorganic components are placed on the receiver substrate,
where each functional inorganic component is in contact
losure is related generally to microfabri-
with one of the conductive-coated protrusio components to the conductive-coated protrusions.
25

BACKGROUND BRIEF DESCRIPTION OF THE DRAWINGS

Microelectromechanical systems (MEMS) technology-
based micromirrors are having an impact on areas such as (SEM) images of an exemplary fabricated micromirror
projection displays, telecommunications, adaptive optics 30 dev

FIGS. 2D-2E show exemplary steps in fabricating inorganic functional components on a donor substrate prior to transfer

EIG. 5 shows frequency response for x- and y-axis
BRIEF SUMMARY 50 rotations, where the resonant frequency is about 1.2 kHz for 50 rotations, where the resonant frequency is about 1.2 kHz for both axes. Inset images show the laser scanning trajectory at 0 Hz (A) and 1.2 Hz (B) ; the scale bars are 1 cm.

(EMS) device.
The micromirror device includes a micromirror compris-
The micromirror device includes a micromirror compris-
mirrors that include both inorganic and organic components inorganic and organic components to be fabricated separately and integrated afterwards may be employed.

An exemplary micromirror device 100 is shown in the include VULCAN® XC-72 carbon black particles produced
scanning electron microscope (SEM) images of FIGS. 1A by Cabot Corporation (Boston, Mass.).
and 1B. A micromirror 10 mirror 102 is supported on an underside thereof by a 5 support and/or the conductive extension portion, may com-
conductive elastomeric support 106 that protrudes from the $\frac{1}{n}$ rise one or more elastomers selected Exercise to permit multi-directional motion of the micromirror 102.

Exercise to permit multi-directional motion of the micromirror 102.

Both the elastomeric substrate 104 and the conductive

elastomeric substrate 104 and lie an additional portion of the elastomeric substrate to form
and inorganic material or different inorganic materials. The
an additional portion of the elastomeric substrate to form
and inorganic material advantageously h a conductive extension portion 112 in electrical contact with 15

the elastomeric substrate 104 under the micromirror 102. The may include metals, alloys, or doped semiconductors. In one
The electrodes 108 are spaced apart from each other and example, the inorganic material may be doped conductive elastomeric support 106. Each electrode 108 doped silicon or other doped semiconductor may include comprises an inorganic material and is in electrical contact one or more suitable dopants, such as boron and/or with an elastomeric contact region 110 protruding from the phorus, preferably at a dopant level sufficient to achieve a elastomeric substrate 104. Each elastomeric contact region resistivity ρ of about 0.01 Ω -cm or 110 comprises an elastomer and may be rendered electrically 25

conductive by an electrically conductive coating thereon. crystalline silicon may be obtained from Ultrasil Corpora-
The micromirror 102 and the electrodes 108 may form a tion (Hayward, Calif.), for example.
parallel-plate more of the elastomeric contact regions 110) and to the 30 micromirror (e.g., via the conductive elastomeric support micromirror (e.g., via the conductive elastomeric support tomeric contact regions. Advantageously, to permit tilting of 106 and the conductive extension portion 112), the micro-
the micromirror in any direction, four (or m 106 and the conductive extension portion 112), the micro-
micromirror in any direction, four (or more) electrodes
mirror 102 may be electrostatically actuated to move in a
may be used in conjunction with four (or more) ela mirror 102 may be electrostatically actuated to move in a may be used in conjunction with four (or more) elastomeric predetermined direction. A voltage bias of at least 10 V, at contact regions. The conductive elastomeric least 20 V or at least 40 V may be suitable for electrostatic 35 actuation. Typically, the voltage bias is 100 V or less, and actuation. Typically, the voltage bias is 100 V or less, and lational and rotational motion of the micromirror in any may be 80 V or less, or 60 V or less. Due to the flexibility direction (e.g., x translation, y translati may be 80 V or less, or 60 V or less. Due to the flexibility direction (e.g., x translation, y translation, z translation, x of the elastomer, the hybrid organic-inorganic micromirror rotation, y rotation, z rotation). device can sustain enormous deformations and accommo-
date three-dimensional motion, such as tip-tilt-piston, with a 40 between the micromirror and the electrodes may be influ-
compact gimbal-less design.
enced by the size

elastomeric support 106 may be integrally formed with the The length and width of the micromirror may be the same, elastomeric substrate 104 as a monolithic elastomeric body 45 as shown in FIGS. 1A and 1B, or different. Th that includes a substantially nonconductive bulk portion 136 the micromirror is typically considerably smaller than the and a number of conductive surface portions 128 (e.g., the length or width (e.g., about 30% or le and a number of conductive surface portions 128 (e.g., the length or width (e.g., about 30% or less, or about 10% or elastomeric contact regions, the conductive elastomeric sup-
less, of the length or width). The electr port, and/or the conductive extension portion). The conductive or smaller dimensions to the micromirror. In the example tive surface portions 128 may be rendered conductive by 50 shown in FIGS. 1A and 1B, the mirror and th tive surface portions 128 may be rendered conductive by 50 shown in FIGS. 1A and 1B, the mirror and the electrodes application of an electrically conductive coating 120 thereto, have dimensions of $500 \times 500 \times 20 \mu m^3$ an and may also be referred to as conductive-coated protrusions respectively, and the conductive elastomeric support (or

rality of conductive particles. The conductive particles may 55 elastomeric support need not be cylindrical, although this be arranged in one or more layers or in another percolating shape may be advantageous to promote sy be arranged in one or more layers or in another percolating shape may be advantageous to promote symmetric tilting of arrangement that covers all or at least a portion of the the micromirror. Generally speaking, the conduc elastomeric region of interest. The conductive particles may meric support may have a height in the range of from about comprise any suitably electrically conductive material, such 10 microns to about 200 microns and a dia as carbon, a metal or an alloy. For example, the conductive 60 from about 5 microns to about 150 microns. The air gap particles may be selected from the group consisting of: between the mirror and the electrodes in the exa particles may be selected from the group consisting of: carbon particles (e.g., carbon black), carbon nanotubes and FIGS. 1A and 1B is 37 microns, but may more generally
metal particles. The size of the conductive particles typically range from about 5 microns to about 100 micr about 1 nm to about 10 microns in average diameter or 65 width, or from about 10 nm to about 1 micron in average diameter or width). Suitable conductive particles may

the conductive elastomeric support 106.
A plurality of (at least two) electrodes 108 are disposed on or polycrystalline in structure. Suitable inorganic materials A plurality of (at least two) electrodes 108 are disposed on or polycrystalline in structure. Suitable inorganic materials
e elastomeric substrate 104 under the micromirror 102 may include metals, alloys, or doped semicond resistivity ρ of about 0.01 Ω -cm or less, about 0.005 Ω -cm or less, or about 0.001 Ω -cm or less. Highly doped single-

contact regions. The conductive elastomeric support may be referred to as a universal joint because it can permit trans-

mpact gimbal-less design.
As described in detail below in reference to FIGS. 2A-2H, support. Typically, the micromirror may have a length and/or As described in detail below in reference to FIGS. 2A-2H, support. Typically, the micromirror may have a length and/or the elastomeric contact regions 110 and the conductive width in the range of from about 10 microns to a less, of the length or width). The electrodes may have similar or smaller dimensions to the micromirror. In the example 8. universal joint) has a cylindrical shape with a height of 80
The electrically conductive coating may comprise a plu-
microns and a diameter of 60 microns. The conductive The electrically conductive coating may comprise a plu-
rail of a diameter of 60 microns. The conductive particles may strategies and a diameter of 60 microns. The conductive
railty of conductive particles. The conductive the micromirror. Generally speaking, the conductive elasto-10 microns to about 200 microns and a diameter or thickness from about 5 microns to about 150 microns. The air gap

micromirror device described above, is now described in reference to FIGS. 2A-2H.

Referring to FIG. 2A, the method entails forming 200 a 2F-2G. For example, the methods described in U.S. Patent plurality of trenches 116 in a surface of a mold 118, and then Application Publication No. 2015-0352586A1, ent plurality of trenches 116 in a surface of a mold 118, and then Application Publication No. 2015-0352586A1, entitled coating 210 surfaces of the trenches 116 with an electrically "Microscale Stamp with Reversible Adhesion." coating 210 surfaces of the trenches 116 with an electrically "Microscale Stamp with Reversible Adhesion," which is conductive coating 120, as shown in FIG. 2B. An uncured hereby incorporated by reference in its entirety, conductive coating 120, as shown in FIG. 2B. An uncured hereby incorporated by reference in its entirety, may be elastomer 122 is applied 220 to the surface of the mold 118 $\,$ s employed. The microscale stamp 132 used f elastomer 122 is applied 220 to the surface of the mold 118 $\frac{1}{10}$ s employed. The microscale stamp 132 used for transfer so as to fill the trenches 116 and cover the surface, as printing may comprise a shape memory p so as to fill the trenches 116 and cover the surface, as printing may comprise a shape memory polymer.
illustrated in FIG. 2C. The uncured elastomer 122 is then partially cured 230 to form a tacky elastomeric body 124 EXAM comprising protruding regions defined by the trenches that contact and attach to the electrically conductive coating 120. 10 An exemplary fabrication procedure of a micromirror
The tackiness of the elastomeric body 124 is due to the device is described here. The method may include

Referring to FIG. 2G, the tacky elastomeric body 124 is assembly of the final devices 100. Referring to FIGS. 2D-2F, removed 240 from the mold and may be flipped over to form silicon mirrors 102 and electrodes 108 may be b a (tacky) receiver substrate 126 . During the removal, the 15 electrically conductive coating 120 remains attached to and electrically conductive coating 120 remains attached to and silicon-on-insulator (SOI) wafers with 20-um-thick and is transferred with the protruding regions, and thus the 3-um-thick device layers. FIG. 2D shows etching 27 is transferred with the protruding regions, and thus the 3-µm-thick device layers. FIG. 2D shows etching 270 of the receiver substrate 126 includes conductive-coated protru-
device layer of an SOI wafer; FIG. 2E shows unde

cally, each functional inorganic component 114 may be placed in contact with one of the conductive-coated protruplaced in contact with one of the conductive-coated protru-
sions 128, as illustrated in FIG. 2G. The receiver substrate (e.g., by a microtip stamp 132) to a receiver substrate 126. is then fully cured 260 to obtain an elastomeric substrate 130 25 The fabrication of the elastomeric body 124 that becomes and to bond the functional inorganic components 114 to the the receiver substrate 126 is shown and to bond the functional inorganic components 114 to the the receiver substrate 126 is shown in FIGS. 2A-2C. In this conductive-coated protrusions 128, as shown in FIG. 2H; example, a three-layer-SU8 mold 118 is patterne conductive-coated protrusions 128, as shown in FIG. 2H; example, a three-layer-SU8 mold 118 is patterned using thus, a hybrid organic-inorganic MEMS device is formed. photolithography and is then silanized to help demoldin thus, a hybrid organic-inorganic MEMS device is formed. photolithography and is then silanized to help demolding
When the MEMS device is a micromirror device 100, the (FIG. 2A). A carbon black (CB)/toluene dispersion is functional inorganic components 114 may include a micro- 30 mirror 102 and a plurality of electrodes 108, each compris-
in the entire mold is left coated with a substantially
ing an electrically conductive material such as a doped
semiconductor, a metal or an alloy, as described ab semiconductor, a metal or an alloy, as described above. The particles on the surface of the mold 118 can be removed by uncured elastomer employed to form the receiver substrate commercial pressure sensitive tapes such that 126 may comprise an uncured polymer selected from the 35 surfaces of the trenches 116 remain coated with a group consisting of uncured polydimethylsiloxane (PDMS) coating 120 of carbon black particles (FIG. 2B). and uncured polyurethane (PU). The mold 118 shown in APDMS precursor 122 is then poured onto the mold 118 FIG. 2A may comprise an epoxy structure formed on a and partially cured at 60° C. for 30 min, as shown in FIG.

coating 120 may entail applying a dispersion of conductive 2G). Referring to FIG. 2F-2G, a deterministic transfer particles in a solvent to the mold and then evaporating the printing technique using a microtip elastomeric solvent, thereby depositing the conductive particles in one or 45 more layers on the surface of the mold and in the trenches. donor substrate 134 and place them on the receiver substrate
The conductive particles may be removed from the surface 126 with about 3 μ m alignment accuracy. U of the mold (e.g., using pressure sensitive tape), leaving the of the pick-and-place procedure via transfer printing, the

heating the uncured elastomer to a suitable curing tempera-
ture for a time duration insufficient to achieve complete condensation reactions. The entire transfer printing-based ture for a time duration insufficient to achieve complete condensation reactions. The entire transfer printing-based
curing or crosslinking. Thus, the uncured elastomer may be microassembly process, including transfer prin partially cured and may have a tacky or sticky consistency. 55 mal b Typically, partial curing is achieved by heating at the curing 90%. temperature of the elastomer (e.g., in the range of about 50° The resulting micromirror device 100 may include an C.-70 $^{\circ}$ C. for PDMS) for a time duration less than half of the elastomeric support or universal jo C.-70 \degree C. for PDMS) for a time duration less than half of the elastomeric support or universal joint 106 extending from full curing duration (e.g., about 1 hour or less at 60 \degree C. for the substrate 104, a top mirror PDMS). Fully curing the tacky elastomeric body may entail ω heating the body at the curing temperature (e.g., in the range heating the body at the curing temperature (e.g., in the range FIGS. 1A, 1B and 2H. In this example, the mirror 102 and of about 50° C.-70° C.) for a time duration sufficient to electrodes 108 are made of highly dope of about 50° C.-70° C.) for a time duration sufficient to electrodes 108 are made of highly doped single crystal achieve complete curing or crosslinking (e.g., at least 2 silicon with minimal resistivity (ρ =0.001 Ω achieve complete curing or crosslinking (e.g., at least 2 silicon with minimal resistivity (ρ =0.001 Ω -cm), which can bours at 60° C. for PDMS).

The tackiness of the elastomeric body 124 is due to the device is described here. The method may include the conly) partial curing of the elastomer. receiver substrate 126.
A plurality of functional inorganic components 114 may 20 photoresist anchors; and FIG. 2F shows etching away of the A plurality of functional inorganic components 114 may 20 photoresist anchors; and FIG. 2F shows etching away of the be placed 250 on the receiver substrate 126. More specifi-
remaining BOX layer using hydrofluoric acid, s remaining BOX layer using hydrofluoric acid, so that the inorganic functional components 114 (silicon mirrors 102

> (FIG. 2A). A carbon black (CB)/toluene dispersion is applied on the mold. After complete evaporation of the commercial pressure sensitive tapes such that only the surfaces of the trenches 116 remain coated with a conductive

substrate (such as silicon wafer or glass), and the trenches 2C. After demolding, the partially cured PDMS body 124, 116 may be formed in the surface of the mold 118 by 40 including conductive PDMS regions 128 and a non-co notolithographic patterning of the epoxy.
The coating of the trenches 116 with the conductive to complete the preparation of a receiver substrate 126 (FIG. printing technique using a microtip elastomeric stamp 132 is employed to pick up the silicon components 114 from the conductive particles only in the trenches, and thereby form-

So approximately 12 hours to form a fully cured elastomeric

So approximately 12 hours to form a fully cured elastomeric g the desired conductive coating.

Partially curing the uncured elastomer may comprise substrate 130. Accordingly, the silicon and PDMS compomicroassembly process, including transfer printing and thermal bonding, may be carried out with a yield of at least about

the substrate 104 , a top mirror 102 on the elastomeric support 106 , and four bottom electrodes 108 , as shown in Placing the functional inorganic components 114 on the 65 184, Dow Corning) is employed as the elastomeric material, tacky receiver substrate 126 may be carried out by transfer and carbon black (CB) particles (VULCAN® XC-7 μ m×20 μ m and 350 μ m×350 μ m×3 μ m, respectively, and the universal joint 106 is 80 μ m in height with a 60 μ m diameter. The invention claimed is:
In this example, the spacing or air gap between the mirror $\frac{1}{1}$ A hybrid organic-inorg

In this example, the spacing or air gap between the mirror s

102 and electrodes 108 is 37 μ m.

To model the static and dynamic behaviors of the exem-

plary micromirror, finite element analysis is performed using

COMS COMSOL 4.3b. Referring to FIGS. 3A-3D, four modes with
resonant frequencies of 0.76 kHz, 1.27 kHz, 4.81 kHz and 10 being supported on an underside thereof by a conduc-
0.04 kHz are contured by model analysis, corresponding 9.94 kHz are captured by modal analysis, corresponding to the elastomeric support protruding from the elasto-
the torsion (z oxis) begins (x ord y oxis) shequen the elastomeric support protruding from the elastomeric supp the torsion $(z - axis)$, bending $(x - and y - axis)$, shearing $(x - and y - axis)$, the distance of the distance of the torsion ($z - axis$) and torsion ($z - axis$) of the elastomeric support ($z - axis$) and torsion ($z - axis$) and the elastomeric support ($z - axis$) y-axis) and tension (z-axis) of the elastomeric support (or functioning as a universal joint and being rendered
electrically conductive by an electrically conductive universal joint). The Young's modulus of PDMS is assumed electrically conductive by a $\frac{1}{2}$ for a electrical production $\frac{1}{2}$ for a electrical production. to be 0.75 MPa in this modal analysis. It is noted that two 15 coating thereon;
modes exist at 1.27 kHz corresponding to the banding a plurality of electrodes disposed on the elastomeric modes exist at 1.27 kHz corresponding to the bending a plurality of electrodes disposed on the elastomeric motions about two orthogonal scanning axes. With perfect substrate under the micromirror, the electrodes being motions about two orthogonal scanning axes. With perfect
symmetry, the micromirror spaced apart from each other and from the micromirror
identical resonant fracuencies. The same holds for the two and being arranged around identical resonant frequencies. The same holds for the two shearing modes.

characterized by applying a DC voltage to the device and contact region protection protect measuring the resultant deflection using an optical profiler
(NT1000, Veeco). The results for both x-and y-axis rota,
wherein, when a voltage bias is applied between the (NT1000, Veeco). The results for both x- and y-axis rota wherein, when a voltage bias is applied between the theory is started when the s tions and z-axis piston from three devices are shown in FIG. 25 micromirror and one or more of the electrodes, the micromirror exhibits micromirror is electrostatically actuated to move in a 4. Due to its symmetric shape, the micromirror exhibits micromirror is electrostatical $\sum_{n=1}^{\infty}$ actuated to move in a move in a move in a movement of the movement of the movement of the movement of the movement of t almost identical DC characteristics about x and y axes.
Spon down occurs under a DC voltage of 00 V. The nighten 2. The hybrid organic-inorganic micromirror device of Snap-down occurs under a DC voltage of 90 V. The piston 2. The hybrid organic-inorganic micromirror device of claim 1, wherein the inorganic material is selected from the stroke is also characterized by applying the same stroke is also characterized by applying the same voltage to
all the electrodes simultaneously. The frequency response of 30 group consisting of: a doped semiconductor, a metal and an all the electrodes simultaneously. The frequency response of $30\frac{\text{grou}}{\text{m}}$ the exemplary device is also characterized, as shown in FIG. allow the exemplary device is also characterized, as shown in FIG.
5. A sinusoidal actuation signal with an DC offset expressed claim 2, wherein the inorganic material is doped silicon. as V(t)=10 sin($2\pi f_{act}$ t)+10 (V) is applied to actuate the claim 2, wherein the inorganic material is doped silicon.
The hybrid organic-inorganic micromirror device of ... mirror about the x- or y-axis while a collimated laser is $\frac{4}{10}$. The nybrid organic-inorganic micromirror device of directed onto the mirror. The length of each reflected pattern 25 claim 2, wherein the inorganic mat directed onto the mirror. The length of each reflected pattern 35 Claim 2, wherein the is measured under different driving fragmenties to selected is measured under different driving frequencies to calculate crystalline structure.

5. The hybrid organic-inorganic micromirror device of the scan angles. The results are fitted to a Lorentzian 5. The hybrid organic - inorganic micromirror device of function in EIG. 5 Beconomic from y ord y original dim 1, wherein the electrically conductive coating comfunction in FIG. 5. Resonant frequencies for x and y-axis claim 1, wherein the electrically conductive particles. rotations are determined to be 1.2 kHz , which match with the entire a purality of conductive particles.
 EXECUTE: 6. The hybrid organic-inorganic micromirror device of values estimated by the prior finite element analysis. The $40\degree$ 6. The hybrid organic - inorganic incromirror device of equal \degree claim 5, wherein the conductive particles are selected from quality factors for both axes are also determined to be equal to 2.1 .

Observations from FIGS. 4 and 5 reveal that the charac-
cities for both y and y axes are almost identical which is $\frac{1}{2}$. The hybrid organic-inorganic micromirror device of teristics for both x and y-axes are almost identical, which is $\frac{7}{10}$. The hybrid organic-inorganic micromirror device of difficult to orbigual using a cumbaled structure. This property Δs claim 1 comprising four o difficult to achieve using a gimbaled structure. This property 45 claim 1 comprising four of the electrodes symmetrical con be quite bondined about the conductive elastomeric support. can be quite beneficial as it fully utilizes the advantage of the
universal joint, e.g., a maximized response along all possible
disponsible
disponsible
disponsible
disponsible
disponsible
disponsible
disponsible
disponsi directions at a single resonant frequency. In addition, the claim 1, wherein the elastomeric substrate, the conductive elastomeric support and the elastomeric contact regions measured scan angles and resonant frequencies of the micro-
mirror dovices in this example are comparable to these of ϵ_0 comprise an elastomer selected from the group consisting of: mirror devices in this example are comparable to those of $\frac{50}{20}$ comprise an elastomer selected from the group consisting original polydimethylicated mirrors, and they validate the polydimethylsiloxane (PDMS) and pol existing microfabricated mirrors, and they validate the
device fabrication capabilities of the transfer printing-based
microscopy by The hybrid organic-inorganic micromirror device of
claim 1, wherein the elastomeric subst

considerable detail with reference to certain embodiments 55 integrally formed as a monolithic elastomeric body com-
thereof other embodiments are possible without departing rising a plurality of conductive surface portion thereof, other embodiments are possible without departing prising a plurality of conductive surface prising the prior substantially non-conductive bulk portion. from the present invention. The spirit and scope of the substantially non-conductive bulk portion.
10. The hybrid organic-inorganic micromirror device of appended claims should not be limited, therefore, to the $\frac{10}{10}$ rhe hybrid organic-morganic incromirror device of decoration of the analysis and analysis of the analysis of the micromirror device of $\frac{1}{10}$ relati description of the preferred embodiments contained herein.
All embodiments that some within the meaning of the Co width in the range of from about 10 microns to about 1 mm. All embodiments that come within the meaning of the 60 widou in the range of from about 10 microns to about 1 mm.
claims, either literally or by equivalence, are intended to be $\frac{11}{2}$. The hybrid organic-inorganic m

Furthermore, the advantages described above are not necessarily the only advantages of the invention, and it is not $* * * * * * *$

structures to form the conductive coating 120. The size of necessarily expected that all of the described advantages will the mirror 102 and the electrodes 108 are $500 \mu m \times 500$ be achieved with every embodiment of t

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- support, each electrode comprising an inorganic mate-
rial and being in electrical contact with an elastomeric The static behavior of the exemplary micromirror is rial and being in electrical contact with an elastomeric sub-
contact region protruding from the elastomeric sub-
	-

the group consisting of: carbon particles, carbon nanotubes and metal particles.

microassembly technique described in this disclosure.
Although the present invention has been described in elastomeric support and the elastomeric contact regions are Although the present invention has been described in elastomeric support and the elastomeric contact regions are
neiderable datail with reference to certain embodiments ss integrally formed as a monolithic elastomeric body

claim 1, wherein the voltage bias is in the range of from about 10 V to about 100 V.